

b 1. (Twice Amended) The article of claim 1 wherein said plurality of layers includes four layers designated the first, second, third, and fourth layers in consecutive numerical order beginning with the layer farthest from the substrate,

C said first layer substantially composed of silicon dioxide and having a refractive index lower than said substrate and having an optical thickness of about one-quarter wavelength at a wavelength between 480 and 560 nanometers,

D said second layer having a refractive index higher than said substrate and between approximately 1.9 and 2.2 and having an optical thickness between about one-quarter and one-third of a wavelength at a wavelength between 480 and 560 nanometers and comprising one of said two layers,

Sub *13* said third layer having a refractive index lower than said second layer and comprising said one other layer,

1 said fourth layer having a refractive index greater than said third layer and comprising the other of said two layers,

2 said third and fourth layers having a total optical thickness less than one-quarter wavelength at a wavelength between 480 and 560 nanometers, and said second and fourth layers being said selected sputtered material.

8. In claim 8, line 6, delete the designation “[DC]”.

17. (Twice Amended) The article of claim 11 wherein said plurality of layers includes four layers designated the first, second, third, and fourth layers in consecutive numerical order beginning with the layer farthest from the substrate,

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said first layer substantially composed of silicon dioxide with a refractive index lower than said substrate and having an optical thickness of about one-quarter wavelength at a wavelength between 480 and 560 nanometers,

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said second layer having a refractive index higher than said substrate and between approximately 1.9 and 2.2 and having an optical thickness between about one-quarter and one-third of a wavelength at a wavelength between 480 and 560 nanometers and comprising one of said two layers,

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said third layer having a refractive index lower than said second layer and comprising said one other layer,

 said fourth layer having a refractive index greater than said third layer and comprising the other of said two layers,

 said third and fourth layers having a total optical thickness less than one-quarter wavelength at a wavelength between 480 and 560 nanometers, and said second and fourth layers being said selected sputtered material.

35. (Amended) An [The] article [of claim 33.] comprising:

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(a) a temperature-sensitive substrate having a melting point lower than glass; and

 (b) an anti-reflection coating comprising a plurality of layers substantially transparent to visible light, wherein;

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(1) a first layer and a third layer are substantially composed of silicon dioxide;
and

(2) a second layer and a fourth layer have refractive indices between
approximately 1.9 and 2.2, and wherein the second and fourth layers are each substantially
composed of and selected from the group consisting of tin oxide, indium oxide, zinc oxide, tin-
doped indium oxide, antimony-doped tin oxide, tin-bismuth oxide, and tin-zinc oxide, wherein
the article has a luminosity of between approximately .18 and .22.

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36. (Amended) An [The] article [of claim 33,] comprising:

(a) a temperature-sensitive substrate having a melting point lower than glass; and

(b) an anti-reflection coating comprising a plurality of layers substantially transparent
to visible light, wherein:

(1) a first layer and a third layer are substantially composed of silicon dioxide;
and

(2) a second layer and a fourth layer have refractive indices between
approximately 1.9 and 2.2, and wherein the second and fourth layers are each substantially
composed of and selected from the group consisting of tin oxide, indium oxide, zinc oxide, tin-
doped indium oxide, antimony-doped tin oxide, tin-bismuth oxide, and tin-zinc oxide, wherein
the second layer has a thickness of between approximately 77.11 and 78.13 mm.

37. (Amended) An [The] article [of claim 33,] comprising:

(a) a temperature-sensitive substrate having a melting point lower than glass; and

(b) an anti-reflection coating comprising a plurality of layers substantially transparent to visible light, wherein;

(1) a first layer and a third layer are substantially composed of silicon dioxide;
and

(2) a second layer and a fourth layer have refractive indices between approximately 1.9 and 2.2, and wherein the second and fourth layers are each substantially composed of and selected from the group consisting of tin oxide, indium oxide, zinc oxide, tin-doped indium oxide, antimony-doped tin oxide, tin-bismuth oxide, and tin-zinc oxide, wherein the fourth layer has a thickness of between approximately 18.64 and 22.83 nm.

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40. (Amended) A method for providing an anti-reflection coating to a substantially plastic substrate, wherein the coating comprises a first, second, third and fourth layers in consecutive numerical order with the first layer being farthest from the substrate, wherein each layer is substantially transparent to visible light, comprising:

providing a plastic substrate;
depositing the first and third layers by reactive sputtering, wherein the first layer is substantially composed of silicon dioxide; and
depositing the second and fourth layers by reactive sputtering, wherein the second and fourth layers have an index of refraction between approximately 1.9 and 2.2 and are each substantially composed of and selected from the group consisting of tin oxide, indium oxide, zinc oxide, tin-doped indium oxide, antimony-doped tin oxide, tin-bismuth oxide, and tin-zinc oxide.

43. (Amended) An anti-reflection coating for a plastic substrate comprising:

a plastic substrate and a coating wherein said coating includes,

and [a plurality of] four layers substantially transparent to visible light[,] designated first,

C5 second, third and fourth layers in consecutive numerical order beginning with the layer farther

from the substrate, said first and third layers comprised of silicon dioxide and said second and

fourth [at least one of said] layers having a refractive index higher than said substrate and

selected from the group consisting of tin oxide, indium oxide, zinc oxide, tin-doped oxide, tin-

bismuth oxide and tin-zinc oxide; and

and [at least one other layer having a refractive index lower than said substrate wherein said at
least one layer is closer to said substrate than said at least one other layer and said at least one
layer and said at least one other layer are adjacent to one another] said second layer having an
optical thickness no greater than about one third of a wavelength at a wavelength of about 480 to
560 nanometers.

and 47. (Amended) A Rock system anti-reflection coating for a plastic substrate comprising a

C6 plastic substrate and said coating wherein the second and fourth layers are substantially

composed of material selected from the group consisting of tin oxide, indium oxide, [zinc oxide,]

tin-doped oxide, tin-bismuth oxide and tin-zinc oxide, and wherein the first layer is substantially

composed of silicon dioxide.

Cancel claims 44-46.